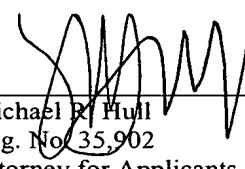




PATENT
30205/37328

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application of: Min Ho Jung et al.)
Serial No.: 09/878,803)
Filed: June 11, 2001)
For: Additive for Photoresist)
Composition for Resist Flow Process)
Group Art Unit: 1752)
Examiner: Yvette C. Thornton)
)
I hereby certify that this paper and the documents referred to as enclosed therewith are being deposited with the United States Postal Service as first class mail, postage prepaid, on **February 27, 2004**, in an envelope addressed to Commissioner for Patents, P.O. Box 1450, Alexandria, Virginia 22313-1450


Michael R. Hull
Reg. No. 35,902
Attorney for Applicants

SECOND AMENDMENT AFTER FINAL (37 C.F.R. § 1.116)

Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

Sir:

Please enter the following amendment in the above-referenced patent application.